

U.S. UTILITY Patent Application

O.I.P.E.

PATENT DATE

SCANNED

Q.A

Pres. 2/11/02 per Mr. [illegible]

APPLICATION NO. 09/966080	CONT/PRIOR F	CLASS 438 430	SUBCLASS 3.1 329	ART UNIT 1756 2812 1756	EXAMINER <i>Danda Rugg</i>
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APPLICANTS

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TIME

Method for fabricating a resist pattern, a method for patterning a thin film and a method for manufacturing a micro device

PTO-204
12/99

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ISSUING CLASSIFICATION

[illegible]

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			Total Claims	Print Claim for O.G.
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FILED WITH: F B I (100-374341) - MEMPHIS - CO-AC-9